



# 제25회 한국반도체학술대회

The 25<sup>th</sup> Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 7일(수), 13:15-14:45

Room I (청옥II+III, 6층)

## K. Memory (Design & Process Technology) 분과 [WI3-K] FeRAM and Transparent ReRAM

WI3-K-1 13:15-13:30	<b>Characterization of Ferroelectric Hafnium Oxide Thin Film</b> Sang Hyun Sung <sup>1</sup> , Do Hyun Kim <sup>1</sup> , Il Suk Kang <sup>2</sup> , and Keon Jae Lee <sup>1</sup> <i><sup>1</sup>Department of Materials Sciences and Engineering, KAIST, <sup>2</sup>Nano Research Division, National NanoFab Center</i>
WI3-K-2 13:30-13:45	<b>New Non-volatile Multi-level Cell Using Epitaxial Strain Effect and Double Ferroelectric Tunnel Junctions</b> Moonhoi Kim, Junbeom Seo, and Mincheol Shin <i>School of Electrical Engineering, KAIST</i>
WI3-K-3 13:45-14:00	<b>Improvement of ZnO Resistive Switching Devices by Metal Thin Layer on ITO Bottom Electrode for Transparent Devices</b> Taehoon Lee <sup>1</sup> , Yong Chan Jung <sup>1</sup> , Sejong Seong <sup>1</sup> , Seon Yong Kim <sup>1</sup> , In-Sung Park <sup>1,2</sup> , and Jinho Ahn <sup>1,2</sup> <i><sup>1</sup>Division of Materials Science and Engineering, Hanyang University, <sup>2</sup>Institute of Nano Science and Technology, Hanyang University</i>
WI3-K-4 14:00-14:15	<b>Investigation on Resistive Switching in Zn-Sn-O Film Using Microwave Irradiation</b> Tae-Wan Kim and Won-Ju Cho <i>Department of Electronic Materials Engineering, Kwangwoon University</i>
WI3-K-5 14:15-14:30	<b>Analysis of LRS Retention Fail based on Joule Heating Effect in InGaZnO RRAM</b> Geumho Ahn, Jun Tae Jang, Daehyun Ko, Hyeri Yu, Haesun Jung, Jihyun Rhee, Hyun-Sun Mo, Sung-Jin Choi, Dong Myong Kim, and Dae Hwan Kim <i>School of Electrical Engineering, Kookmin University</i>
WI3-K-6 14:30-14:45	<b>Capacitorless 1T-DRAM Device</b> Sehyun Kwon <sup>1</sup> , Minho Choi <sup>1</sup> , In-sung Park <sup>2</sup> , Yong Tae Kim <sup>3</sup> , and Jinho Ahn <sup>1,2</sup> <i><sup>1</sup>Department of Materials Science and Engineering, Hanyang University, <sup>2</sup>Institute of Nano Science and Technology, Hanyang University, <sup>3</sup>KIST</i>